



- Rate at which electrons from conduction band will be captured by traps is ~ no of conduction band electrons, no of empty traps

$$R_{cn} = C_n N_t [1 - f(E_t)] n$$

$$R_{en} = E_n N_t f(E_t)$$

$$f(E_t) = \frac{1}{1 + \exp\left(\frac{E_t - E_F}{kT}\right)}$$

At thermal equilibrium,

$$R_{cn} = R_{en} \text{ for } n_0$$

$$C_n N_t [1 - f(E_t)] n_0 = E_n N_t f(E_t)$$

$$E_n = n_0 C_n \left[ \frac{1 - f(E_t)}{f(E_t)} \right] = n_0 C_n \exp\left(\frac{E_t - E_F}{kT}\right) = n_1 C_n$$

$$n_1 = n_0 \exp\left(\frac{E_t - E_F}{kT}\right)$$

Thus, the net rate at which electrons are being captured from the conduction band

From processes 3 and 4, similarly, the net rate at which holes are being captured from the valence band



- Only when  $N_t$  is low compared to the doping level, we can assume

Equating the two expressions for  $R_n$  and  $R_p$  in the previous slide,

$$\begin{aligned}
 n p - n_i^2 & \\
 &= (n_0 + \delta n)(p_0 + \delta p) - n_i^2 \\
 &= \delta p (n_0 + p_0 + \delta p)
 \end{aligned}$$

$$N_t = \frac{C_n C_p N_t (n_0 + p_0)}{C_n (n_0 + n_1) + C_p (p_0 + p_1)}$$

low level injection



• In the limit when  $n_0 \gg p_0, \delta p$ , then

n type sample  
 $\tau = \tau_{p0} = \frac{1}{C_p N_t}$

• In the limit when  $p_0 \gg n_0, \delta n$ , then

p type sample  
 $\tau = \tau_{n0} = \frac{1}{C_n N_t}$

• In between for small values of  $\delta p$  and  $\delta n$  (low level injection), we have

$$\tau = \frac{\tau_{p0}(n_0 + n_1)}{(n_0 + p_0)} + \frac{\tau_{n0}(p_0 + p_1)}{(n_0 + p_0)}$$

$$E_t = E_i$$

$$n_0 = p_0 = n_i$$

$$n_1 = p_1 = n_i$$

$$\tau = \tau_{p0} + \tau_{n0}$$

